



Pivotal's Sensor X™ Achieves a Design Win With a Leading OEM for Low Exposed Area Etch End Point

ATOMIC LEVEL VISION ALLOWS FOR ROBUST END POINTING OF LOW EXPOSED AREA OXIDE ETCH PROCESSES

Pleasanton, CA.—July 9, 2007—Pivotal Systems Corporation today announced achieving a design win with a major OEM, using Sensor X™ to provide end point capabilities for low exposed area oxide etch applications. “The SX-700 offers the best and easiest to use end point performance for oxide etch end point applications because of its ability to excite silicon at the atomic level,” said Chuck Borowski, Pivotal’s Director of Product Marketing. Borowski further pointed out that tracking the silicon atomic signal during oxide etches allows for:

1. High signal to noise performance for etch end point
2. Ability to end point via and contact etches where the exposed area is below 1%
3. One simple silicon based end point algorithm independent of chamber type, recipe or device

“Achieving this OEM design win is proof that Sensor X fills a critical need that existing end point sensor technology cannot meet. We expect more OEMs to adopt this technology as IDMs conclude that fixed time via and contact etches are no longer possible at smaller technology nodes,” said Mukund Venkatesh, Pivotal’s Vice President of Marketing and Business Development.

About Pivotal Systems

Pivotal Systems Corporation provides best-in-class monitoring and process control technology for the semiconductor manufacturing industry. Pivotal’s vision is to enable an order of magnitude increase in fab productivity and capital efficiency for current and future technology nodes. This vision is achieved through its real time in situ process monitoring and control solutions. Founded in 2003 and based in Pleasanton, California, the company is led by veterans from the semiconductor and high-tech industries. For more information about Pivotal, please visit www.pivotalsys.com, or send an email to info@pivotalsys.com.